

**Search Notes**

Application No.

10/706,090

Applicant(s)

SUGAMOTO ET AL.

Examiner

Granvill D Lee, Jr

Art Unit

2825

**SEARCHED**

Class	Subclass	Date	Examiner
438	745,689	9/1/2004	GL
438	693,704	9/1/2004	GL
438	494,498	9/1/2004	GL
438	504	9/1/2004	GL
438	734-735	9/1/2004	GL
216	56,62	9/1/2004	GL
216	103-109	9/1/2004	GL
156	345.1	9/1/2004	GL
156	345.11	9/1/2004	GL
156	912-915	9/1/2004	GL

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
second solution, oxidative acid, oxidizing agent, crystal defects, secco etch, cleaning, selective etching, HF, defect-free	9/1/2004	GL